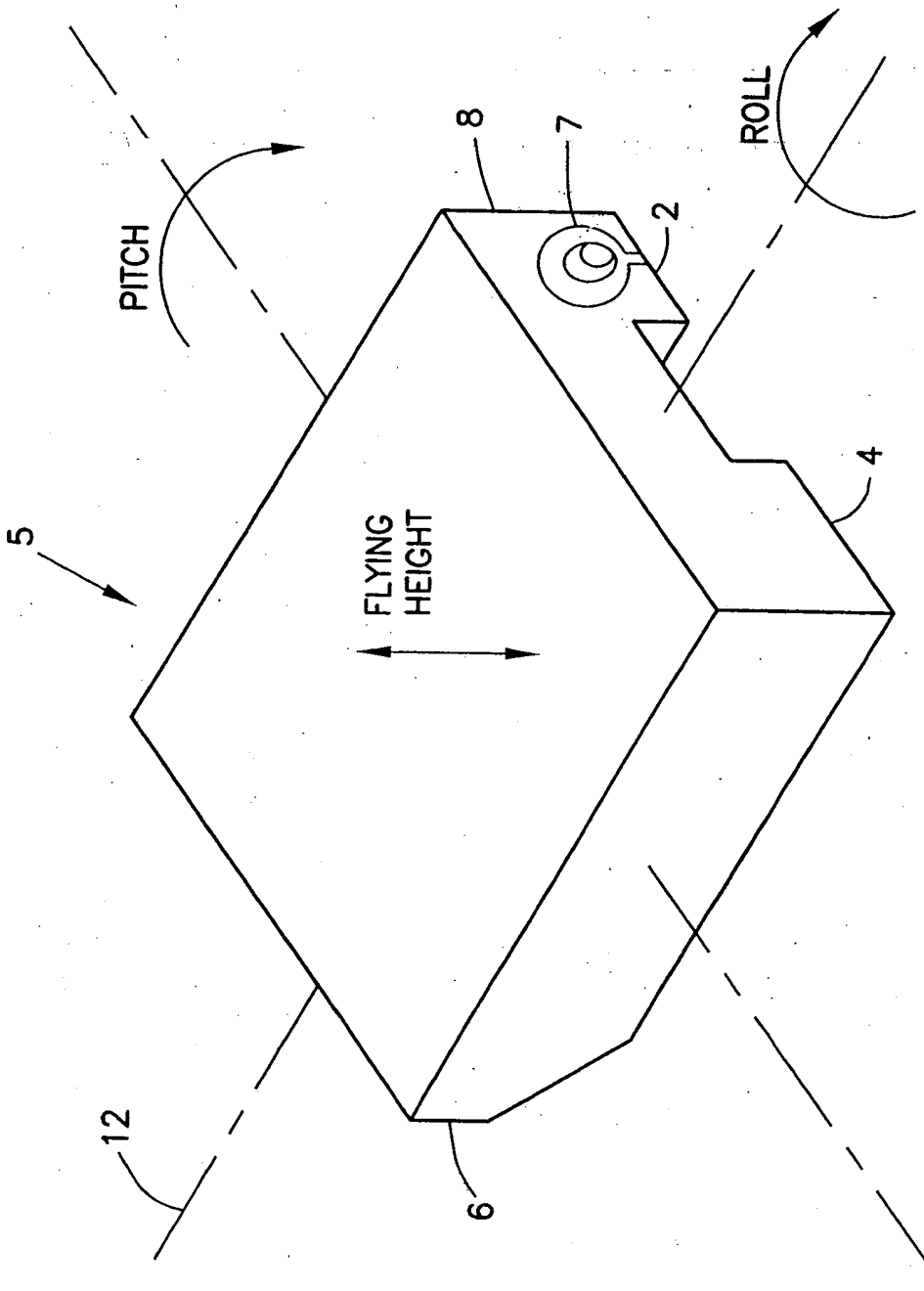
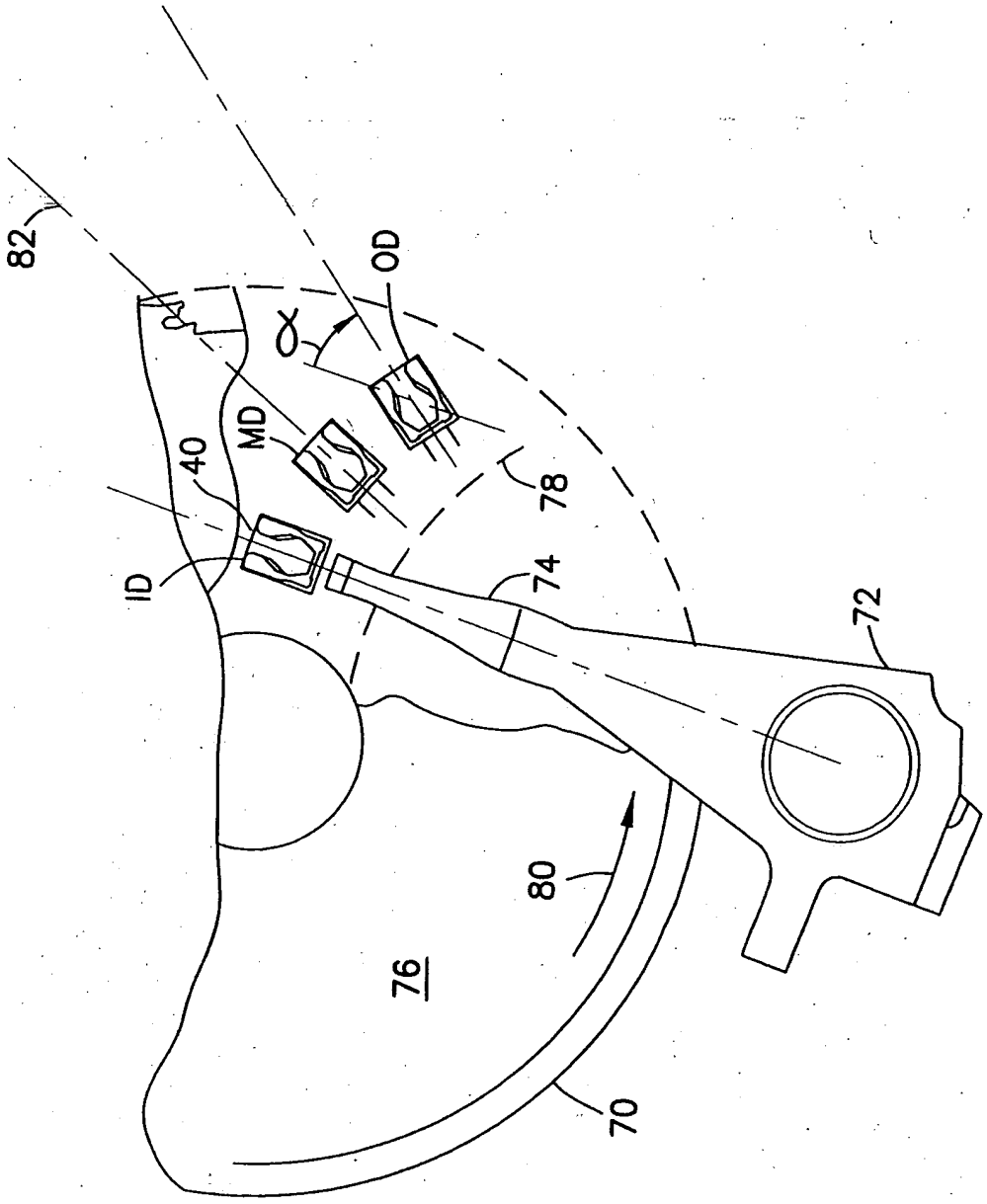


Fig. 1
Prior Art

Fig. 2



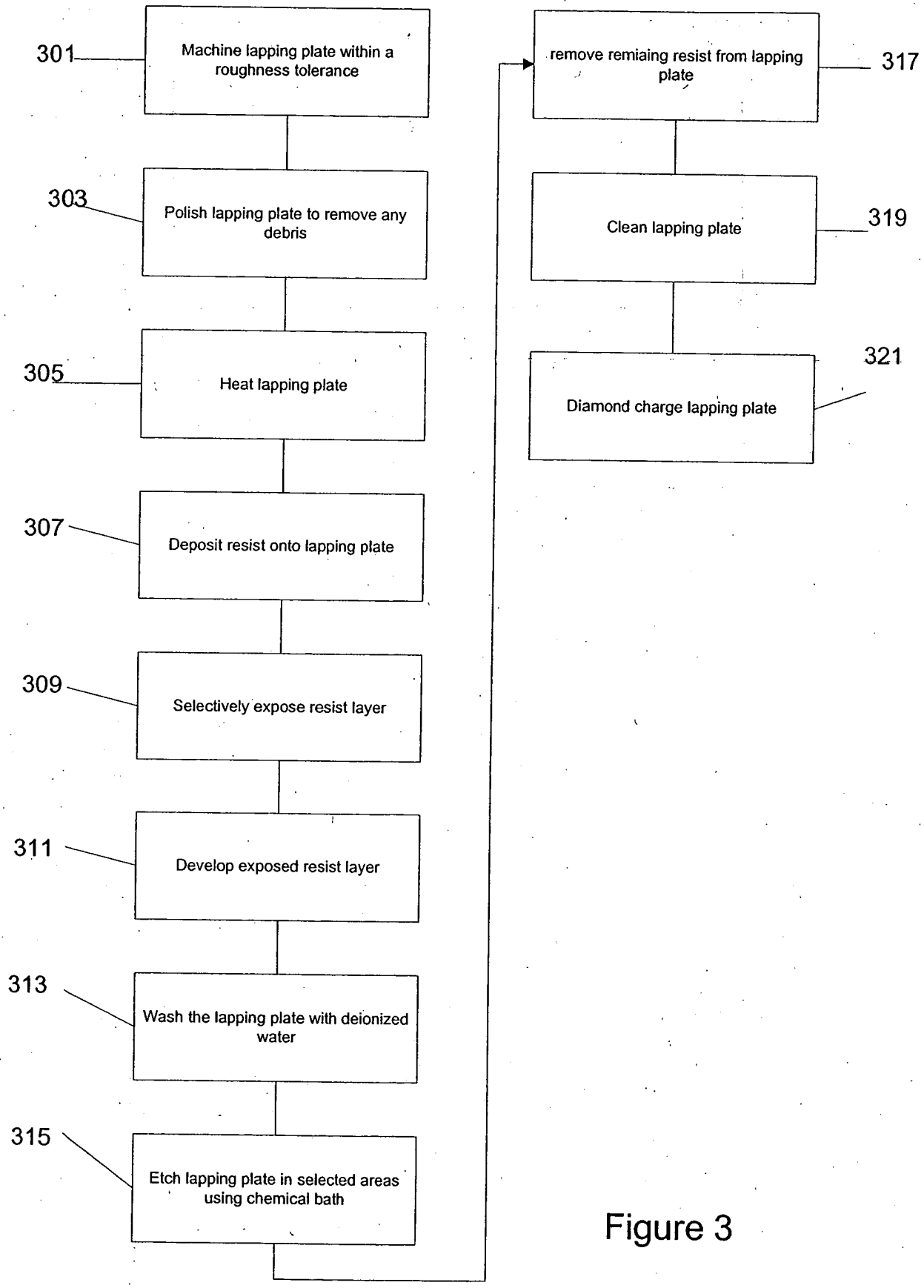

301
Machine lapping plate within a roughness tolerance
303
Polish lapping plate to remove any debris
305
Heat lapping plate
307
Deposit resist onto lapping plate
309
Selectively expose resist layer
311
Develop exposed resist layer
313
Wash the lapping plate with deionized water
315
Etch lapping plate in selected areas using chemical bath
317
remove remiaing resist from lapping plate
319
Clean lapping plate
321
Diamond charge lapping plate

Figure 3

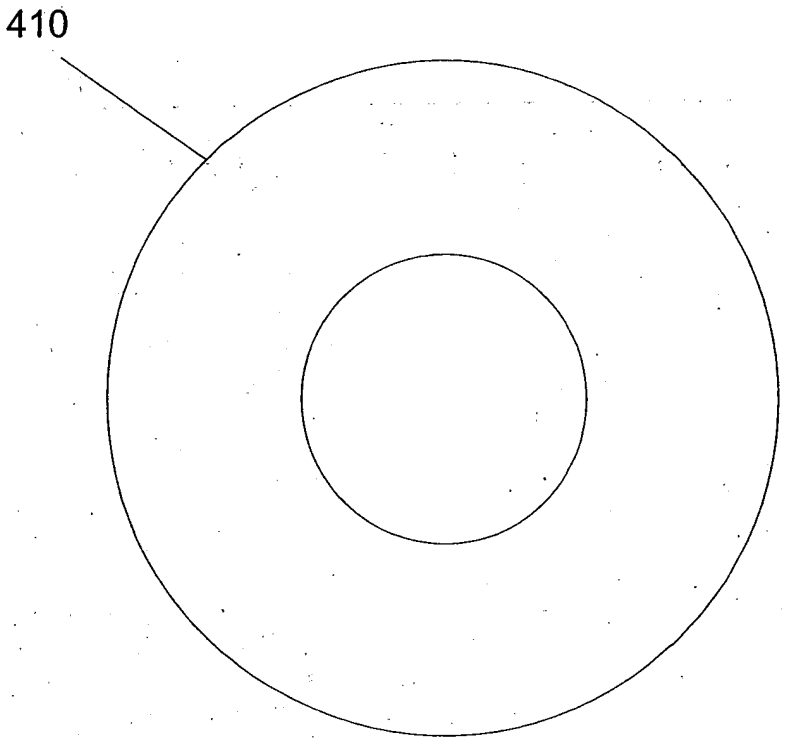


Figure 4a

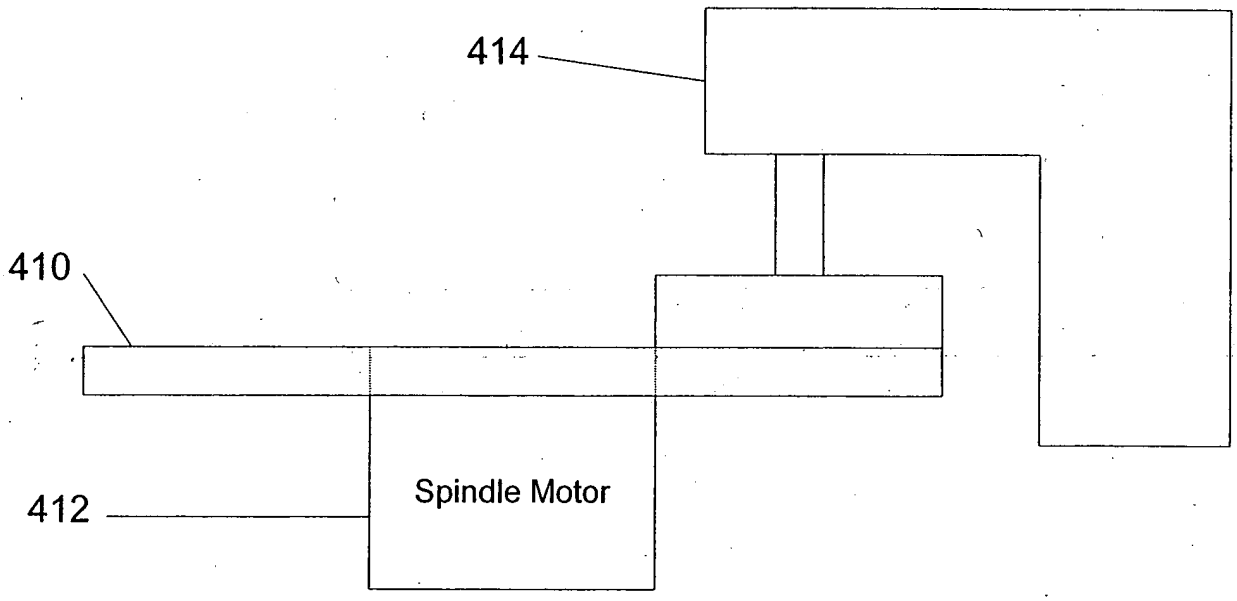


Figure 4b

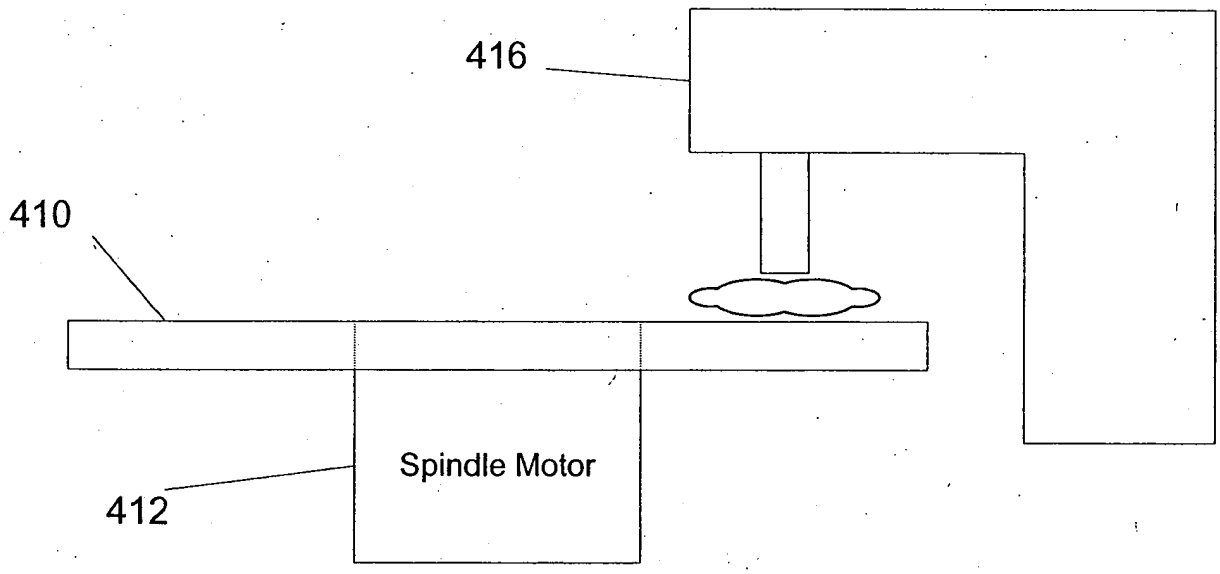


Figure 4c

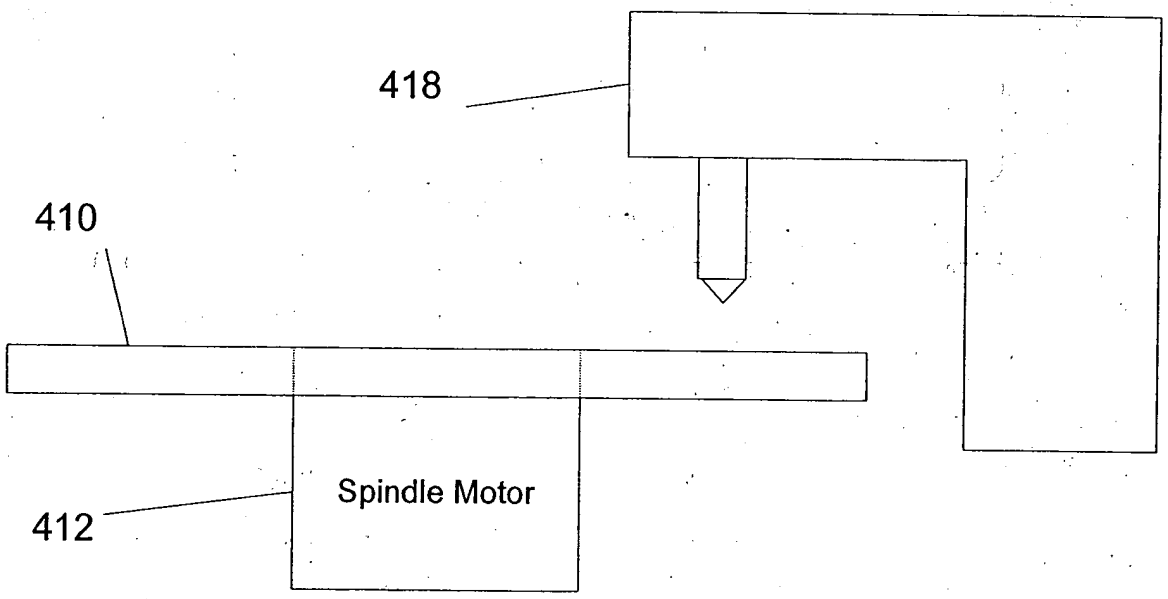


Figure 4d

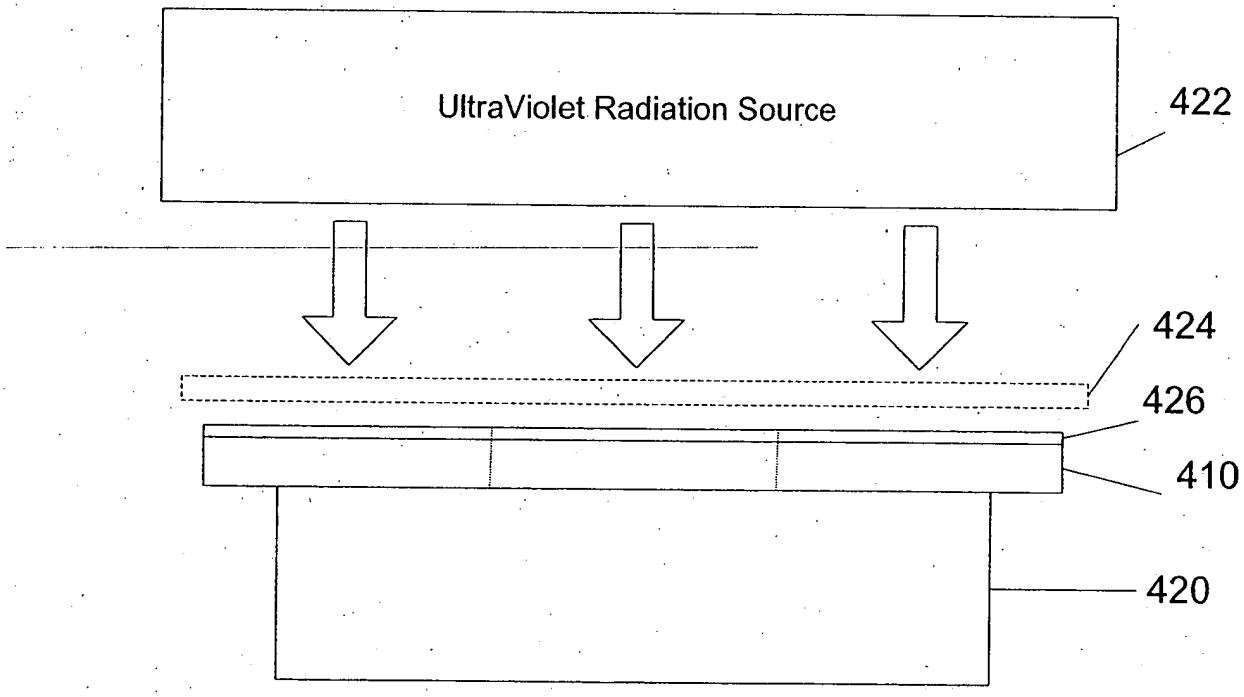


Figure 4e

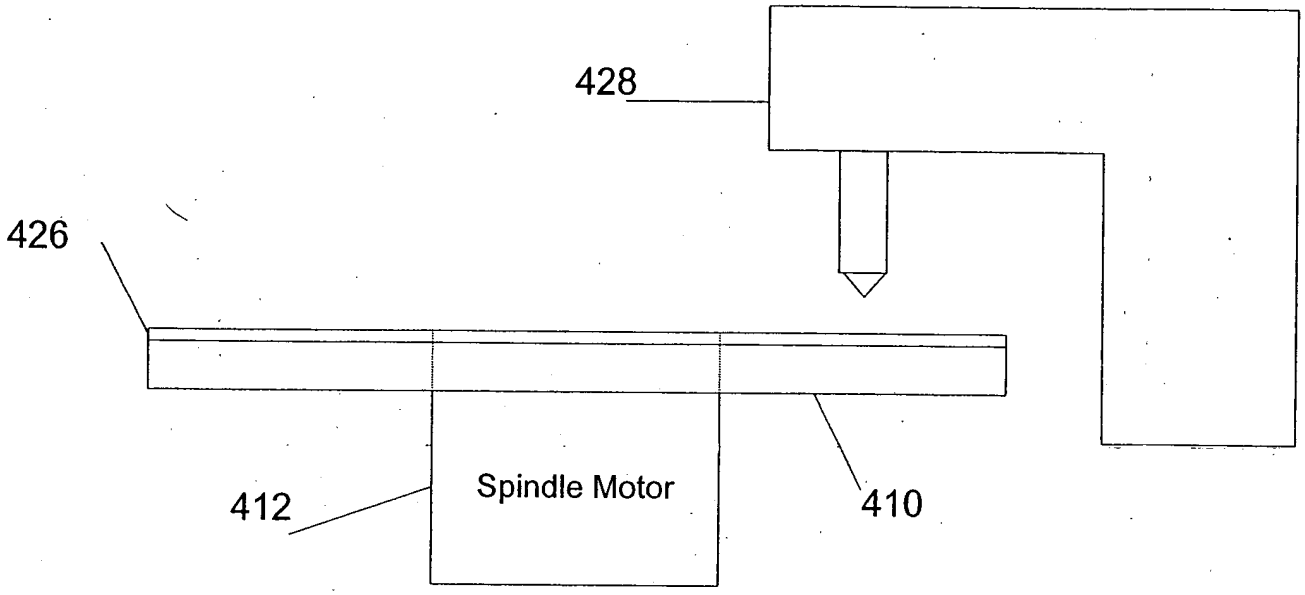


Figure 4f

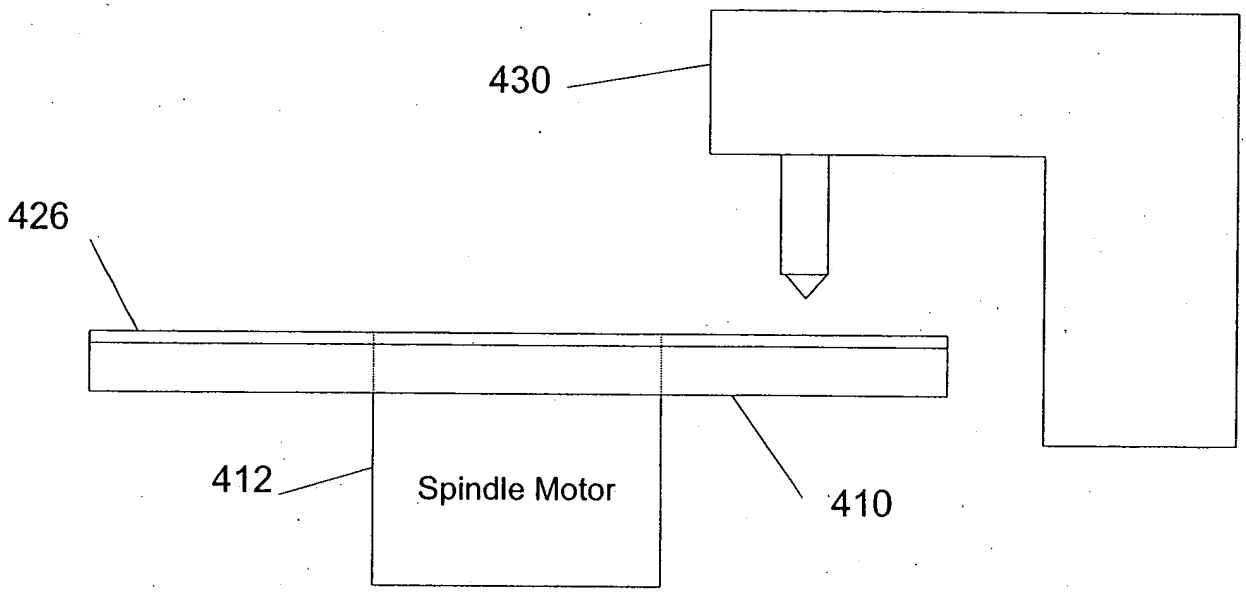


Figure 4g

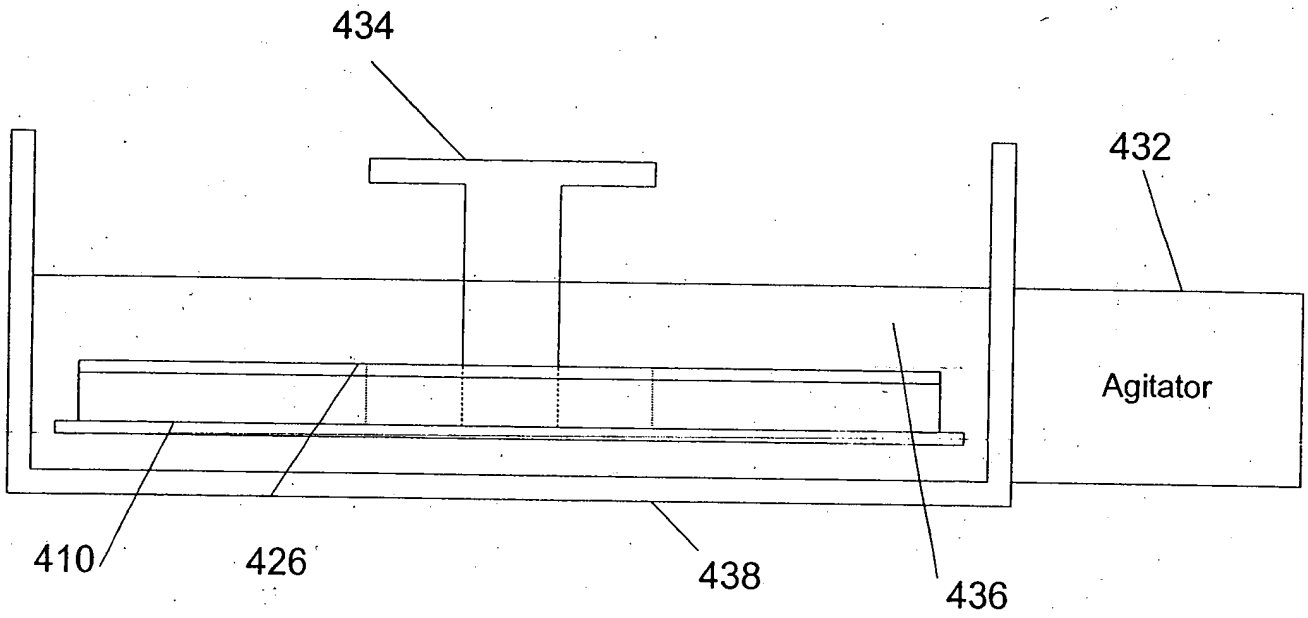


Figure 4h

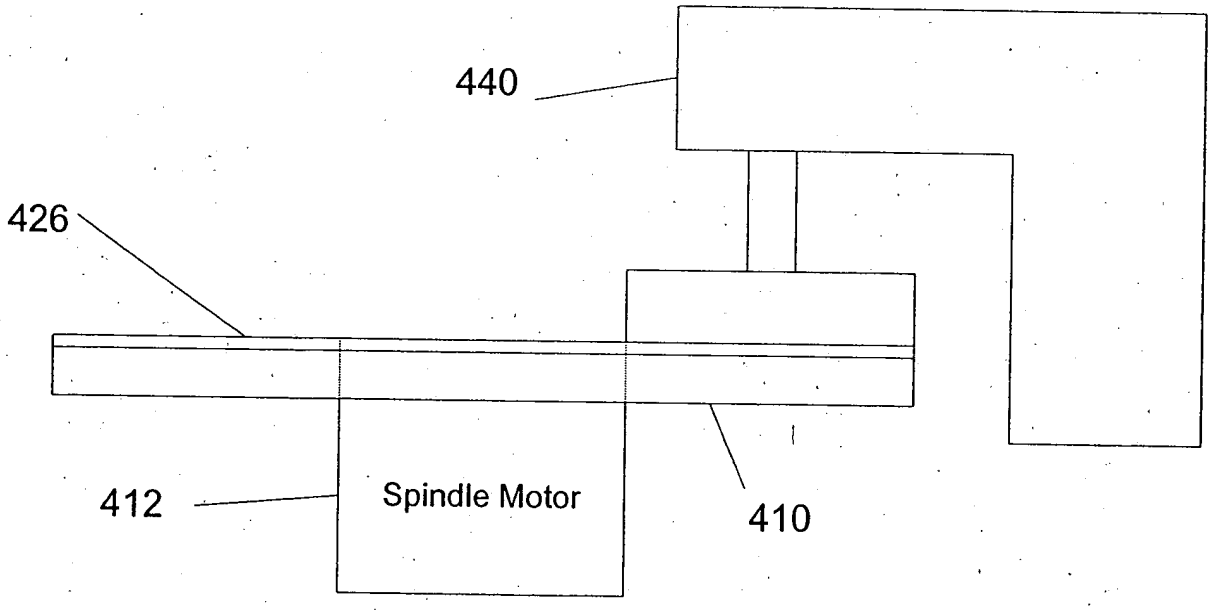


Figure 4i

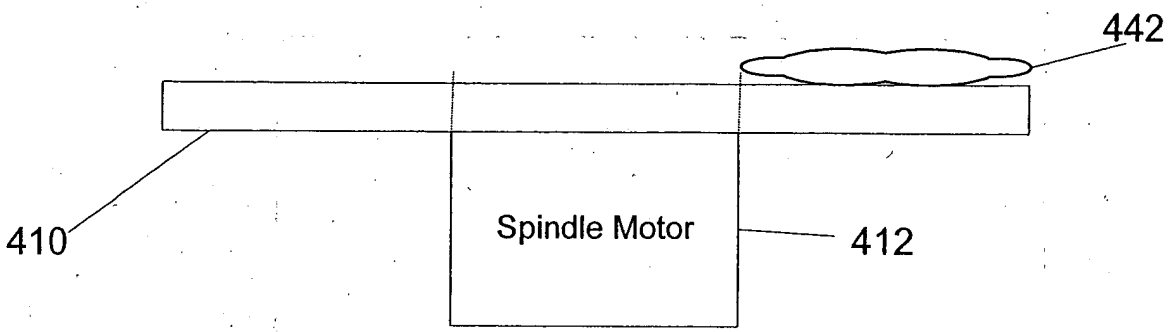


Figure 4j

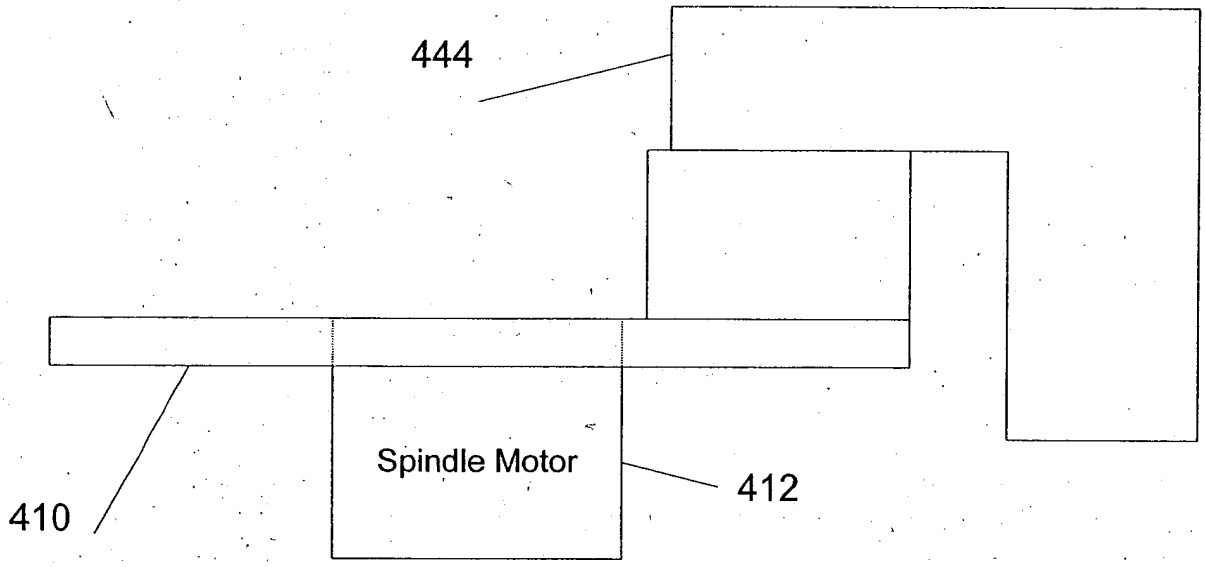


Figure 4k

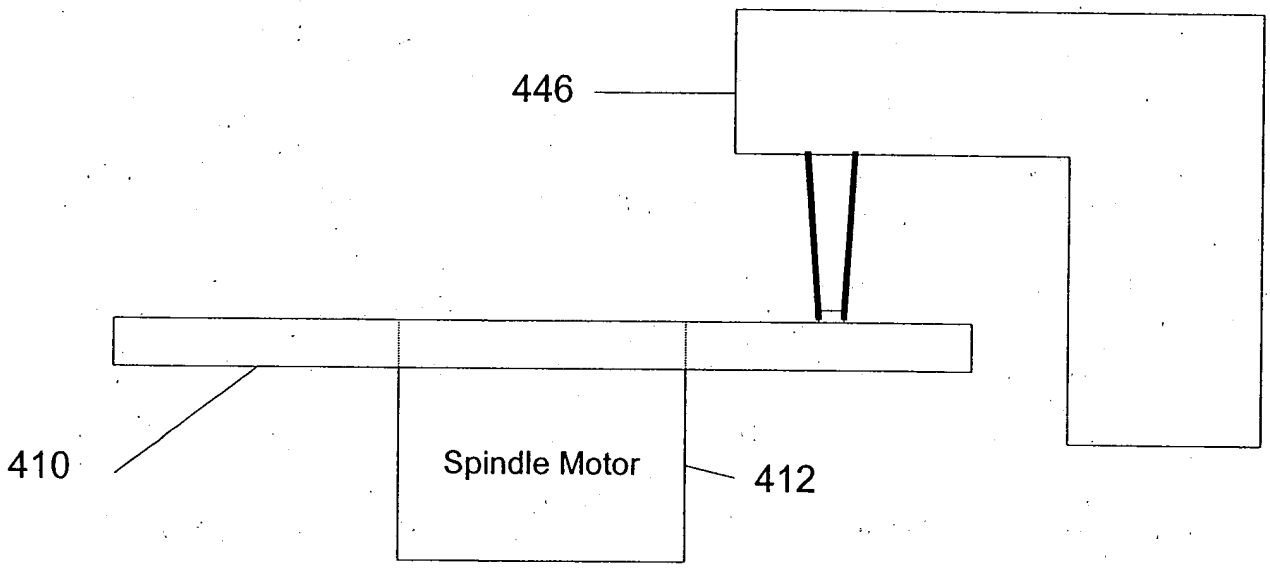


Figure 4I